| # | Paper # | Area | Presenter (First) | Presenter (Last) | Company | Title | Duration | Start | Finish |
|---|---|---|---|---|---|---|---|---|---|
| **All Times are local time in Berkeley, CA, USA (PDT)** | | | | | | | | | |
| **On June 6-7, 2026 Short Courses are on-line only. From June 8-11, 2026 the workshop is in-person only.** | | | | | | | | | |
| ***Version: April 14, 2026 . For questions or comments please contact info@euvlitho.com*** | | | | | | | | | |
| ***Short Course*** | | | | | | | | | |
| ***Short Course:* EUV and Soft X-Ray Sources** | | | | | | | | | |
| **8:30 AM, Saturday, June 6, 2026, Berkeley, CA (Course is held online Only)** | | | | | | | | | |
| **All Times are for Berkeley, CA, USA. Please estimate times for your own time zones, for this live event.** | | | | | | | | | |
| ***Instructors: Gerry O'Sullivan, Marcelo Ackermann, Henry Kapteyn, Dinh Nguyen and Ladislav Pina*** | | | | | | | | | |
| *Short Courses and EUVL & Source Workshop require separate registrations. Please visit www.euvlitho.com for information.* | | | | | | | | | |
| | | | | | | ***AV Test and Speaker Check-in*** | 0:15 | 8:30 AM | 8:45 AM |
| | 1 | | Gerry | O'Sullivan | UCD | Physics of EUV and Short Wavelength Sources with Focus on Atomic Physics | 1:30 | 8:45 AM | 10:15 AM |
| | | | | | | **Break** | 0:15 | 10:15 AM | 10:30 AM |
| | 2 | | Marcelo | Ackerman | University of Twente / | EUV Multilayers | 1:30 | 10:30 AM | 12:00 PM |
| | | | | | | **Lunch Break** | 0:30 | 12:00 PM | 12:30 PM |
| | 3 | | Henry | Kapteyn | Univ of Colorado and K&M Labs | Fundamentals and Applications of Coherent High Harmonic EUV Sources | 1:30 | 12:30 PM | 2:00 PM |
| | | | | | | **Break** | 0:15 | 2:00 PM | 2:15 PM |
| | 4 | | Dinh | Nguyen | xLight | Module 5: FEL for EUV Lithography | 1:30 | 2:15 PM | 3:45 PM |
| | | | | | | **Break** | 0:15 | 3:45 PM | 4:00 PM |
| | 5 | | Ladislav | Pina | CTU in Prague | Grazing Incidence Optics and Applications for EUV and Soft X-ray Sources | 1:30 | 4:00 PM | 5:30 PM |
| **Short Course Adjourned** | | | | | | | | | |

| # | Paper # | Area | Presenter (First) | Presenter (Last) | Company | Title | Duration | Start | Finish |
|---|---|---|---|---|---|---|---|---|---|
| ***Short Course*** | | | | | | | | | |
| ***Short Course:* EUV Lithography** | | | | | | | | | |
| **8:30 AM, Sunday, June 7, 2026, Berkeley, CA (Course is held online Only)** | | | | | | | | | |
| **All Times are for Berkeley, CA, USA. Please estimate times for your own time zones, for this live event.** | | | | | | | | | |
| ***Instructors: Vivek Bakshi (EUV Litho, Inc.), Sebastian Brueck (Carl Zeiss), Sangsul Lee (Postech University), Patrick Naulleau (EUV Tech), and Jan van Shoot (ASML)*** | | | | | | | | | |
| *Short Courses and EUVL & Source Workshop require separate registrations. Please visit www.euvlitho.com for information.* | | | | | | | | | |
| | | | | | | | | | |
| | | | | | | ***AV Test and Speaker Check-in*** | 0:00 | 8:30 AM | 8:30 AM |
| | 1 | | Vivek | Bakshi | EUV Litho | Introduction to EUVL, EUVL Extension and EUV Sources | 1:30 | 8:30 AM | 10:00 AM |
| | | | | | | **Break** | 0:15 | 10:00 AM | 10:15 AM |
| | 2 | | Jan | van Schoot | ASML | High NA EUVL | 1:30 | 10:15 AM | 11:45 AM |
| | | | | | | **Lunch Break** | 0:30 | 11:45 AM | 12:15 PM |
| | 3 | | Patrick | Naulleau | EUV Tech | EUVL Imaging and Patterning | 1:30 | 12:15 PM | 1:45 PM |
| | | | | | | **Break** | 0:15 | 1:45 PM | 2:00 PM |
| | 4 | | Sebastian | Brueck | Carl Zeiss | EUVL Optics | 1:15 | 2:00 PM | 3:15 PM |
| | | | | | | **Break** | 0:15 | 3:15 PM | 3:30 PM |
| | 5 | | Sangsul | Lee | Postech | EUVL Masks | 1:30 | 3:30 PM | 5:00 PM |
| **Short Course Adjourned** | | | | | | | | | |

| # | Paper # | Area | Presenter (First) | Presenter (Last) | Company | Title | Duration | Start | Finish |
|---|---|---|---|---|---|---|---|---|---|
| | | | | | | **Day 1 (AM): Blue-X Technical Working Group (TWG) Meeting** | | | |
| | | | | | | ***In-person Meeting, Open to Blue-X TWG Members only*** | | | |
| | | | | | | **8:30 AM - 5:00 PM , Monday, June 8, 2026, Pauley Ballroom, UC Berkeley, CA** | | | |
| | | | | | | ***Breakfast, Coffee and Check-in*** | 0:30 | 8:00 AM | 8:30 AM |
| | | | | | | **Technical Working Group Discussions and Blue-X TWG Member Presentations 9:30 AM - 4:00 PM** | | | |
| | | | | | | **Session 1: Blue-X Opening Session. Session Chair: Allen Gabor (IBM)** | | | |
| 1 | Intro-1 | Blue-X TWG | Vivek | Bakshi | EUV Litho | Announcements | 0:05 | 8:30 AM | 8:35 AM |
| 1 | B1 | Blue-X TWG | Vivek | Bakshi | EUV Litho | Blue-X TWG: Status and Plans | 0:15 | 8:35 AM | 8:50 AM |
| | | | | | | **Session 2: Blue-X Keynote, Session Chair: Allen Gabor (IBM)** | | | |
| 2 | B4 | Blue-X Keynote | Takeo | Watanabe | University of Hyogo | The Lithographic Benefit and Technical Issue of Shortening the Wavelength of EUVL | 0:30 | 8:50 AM | 9:20 AM |
| 2 | B1 | Blue-X Keynote | Ralph | Dammel | Merck / EMD Electronics | Dose Requirements for LCDU Control at Blue-X Wavelengths | 0:30 | 9:20 AM | 9:50 AM |
| 2 | B3 | Blue-X Keynote | Yuri | Ralchenko | UMD | Overview of Atomic Spectroscopic Data for the Blue-X Water Window Program | 0:30 | 9:50 AM | 10:20 AM |
| 2 | B2 | Blue-X Keynote | Vladimir | Liberman | MIT LL | Robust Design and Material Optimization for Multilayer Coatings for Blue-X Wavelengths | 0:30 | 10:20 AM | 10:50 AM |
| | | | | | | **Break** | **0:15** | **10:50 AM** | **11:05 AM** |

| # | Paper # | Area | Presenter (First) | Presenter (Last) | Company | Title | Duration | Start | Finish |
|---|---|---|---|---|---|---|---|---|---|
| **Monday, June 8, 2026, Pauley Ballroom, UC Berkeley, CA** | | | | | | | | | |
| **Session 3: Blue-X-Optics, Session Co-Chairs: TBA** | | | | | | | | | |
| 3 | B46 | Blue-X-Optics | Antonio | Checco | Veeco | Blue-X ML Optics Sub - TWG Update | 0:10 | 11:05 AM | 11:15 AM |
| 3 | B45 | Blue-X-Optics | Marcelo | Ackermann | University of Twente | TBA | 0:15 | 11:15 AM | 11:30 AM |
| 3 | B43 | Blue-X-Optics | Naoki | Hayase | University of Hyogo | Improved Mo2N/B multilayer for beyond EUV lithography | 0:15 | 11:30 AM | 11:45 AM |
| 3 | B44 | Blue-X-Optics | Takeo | Ejima | Tohoku University (SRIS) | Deposition System for Reflective Multilayers Below 6.x nm Enabled by Sub-nm Thickness Control | 0:15 | 11:45 AM | 12:00 PM |
| 3 | B41 | Blue-X-Optics | Eric | Gullikson | LBNL | ML Project Update (Tentative Title) | 0:15 | 12:00 PM | 12:15 PM |
| 3 | B42 | Blue-X-Optics | Ladislav | Pina | Rigaku | Grazing Incidence Mirror for FEL Water Window Beams | 0:15 | 12:15 PM | 12:30 PM |
| | | | | | | **Lunch** | **1:00** | **12:30 PM** | **1:30 PM** |

| # | Paper # | Area | Presenter (First) | Presenter (Last) | Company | Title | Duration | Start | Finish |
|---|---|---|---|---|---|---|---|---|---|
| **Monday, June 8, 2026, Pauley Ballroom, UC Berkeley, CA** | | | | | | | | | |
| **Session 4: Source Sub-TWG, Session Co-Chairs: TBA** | | | | | | | | | |
| 4 | B67 | Blue-X-Source | TBA | | | Blue-X Plasma Sources Sub - TWG Update | 0:10 | 1:30 PM | 1:40 PM |
| 4 | B63 | Blue-X-Source | Yusuke | Teramoto | Ushio | Short-Wavelength Radiation from a Regenerative Target Laser-Produced Plasma Source | 0:15 | 1:40 PM | 1:55 PM |
| 4 | B66 | Blue-X-Sources | Mariko | Yamaguchi | RIC | Laser-Driven, High Brilliance Sources in the BEUV to Tender X-ray Range | 0:15 | 1:55 PM | 2:10 PM |
| 4 | B65 | Blue-X-Source | Tommy | Sebastian | MIT LL | Development and Testing of Liquid Nitrogen Droplet Generator | 0:15 | 2:10 PM | 2:25 PM |
| 4 | B61 | Blue-X-Source | Yosuke | Honda | KEK | FEL Development Status Update | 0:15 | 2:25 PM | 2:40 PM |
| 4 | B64 | Blue-X-Source | Brandon | Holybee | xLight | Impact of EUV FEL Exposure on Photoresist Sensitivity and Chemical Mechanisms | 0:15 | 2:40 PM | 2:55 PM |

| # | Paper # | Area | Presenter (First) | Presenter (Last) | Company | Title | Duration | Start | Finish |
|---|---|---|---|---|---|---|---|---|---|
| **Monday, June 8, 2026, Pauley Ballroom, UC Berkeley, CA** | | | | | | | | | |
| **Session 5: Blue-X Mask, Session Co-Chairs: TBA** | | | | | | | | | |
| 5 | B21 | Blue-X-Mask | Meng / Ben | Lee / Eynon | Veeco / Lam | Blue-X Mask Sub - TWG Update | 0:10 | 2:55 PM | 3:05 PM |
| 5 | B22 | Blue-X-Mask | Marcus | Benk | CXRO | SHARP Photomask Imaging: Supporting the Extension of EUV Lithography Beyond 0.55NA and 13.5nm Wavelength | 0:15 | 3:05 PM | 3:20 PM |
| | | | | | | **Break** | **0:15** | **3:20 PM** | **3:35 PM** |

| # | Paper # | Area | Presenter (First) | Presenter (Last) | Company | Title | Duration | Start | Finish |
|---|---|---|---|---|---|---|---|---|---|
| **Monday, June 8, 2026, Pauley Ballroom, UC Berkeley, CA** | | | | | | | | | |
| **Session 6: Blue-X Metrology, Session Co-Chairs: TBA** | | | | | | | | | |
| 6 | B32 | Blue-X-Metrology | TBA | | | Blue-X ML Optics Sub - TWG Update | 0:10 | 3:35 PM | 3:45 PM |
| 6 | P33 | Blue-X-Metrology | Victor | Soltwisch | PTB | Infrastructure for the Water Window: Status and Future of Optical Metrology | 0:15 | 3:45 PM | 4:00 PM |
| 6 | B31 | Blue-X-Metrology | Ben | Zeiger | Luxel | Transmission Filters for <13.5 nm Lithography | 0:15 | 4:00 PM | 4:15 PM |

| # | Paper # | Area | Presenter (First) | Presenter (Last) | Company | Title | Duration | Start | Finish |
|---|---|---|---|---|---|---|---|---|---|
| **Monday, June 8, 2026, Pauley Ballroom, UC Berkeley, CA** | | | | | | | | | |
| **Session 7: Blue-X Resist, Session Co-Chairs: TBA** | | | | | | | | | |
| 7 | B52 | Blue-X - Resist and Patterning | TBA | | | Blue-X Resist Sub - TWG Update | 0:10 | 4:15 PM | 4:25 PM |
| 7 | B51 | Blue-X - Resist and Patterning | Dario | Goldfarb | IBM | Interactions of Polarized EUV Light with Resist | 0:15 | 4:25 PM | 4:40 PM |
| | | | | | | **Break** | 0:20 | 4:40 PM | 5:00 PM |
| | | | | | | **Joint Reception with 2026 EUVL and Source Workshop Attendees / Registration** | 1:00 | 5:00 PM | 6:00 PM |
| **Blue-X TWG Meeting Adjourned** | | | | | | | | | |

| # | Paper # | Area | Presenter (First) | Presenter (Last) | Company | Title | Duration | Start | Finish |
|---|---|---|---|---|---|---|---|---|---|
| | | | | | | | | | |

# Day 1 (PM): 2026 EUVL and Source Workshop

# Joint Reception: Blue- X TWG and 2026 EUVL and Source Workshop

## Monday, June 8, 2026, Pauley Ballroom, UC Berkeley, CA

| Title | Duration | Start | Finish |
|---|---|---|---|
| Registration and Reception | 1:00 | 5:00 PM | 6:00 PM |

**Joint Reception Adjourned**



EUV Litho, Inc.
www.euvlitho.com

| # | Paper # | Area | Presenter (First) | Presenter (Last) | Company | Title | Duration | Start | Finish |
|---|---|---|---|---|---|---|---|---|---|
| | | | | | | | | | |

# Day 2: 2026 EUVL and Source Workshop

## 8:30 AM - 7:00 PM, Tuesday, June 9, 2026, Pauley Ballroom, UC Berkeley, CA

***Please see Abstract Book on website www.euvlitho.com for abstracts and co-author(s) information by paper #.***

***Session 1: Keynote-1, Session Chair: Patrick Naulleau (EUV Tech)***

| # | Paper # | Area | Presenter (First) | Presenter (Last) | Company | Title | Duration | Start | Finish |
|---|---|---|---|---|---|---|---|---|---|
| | | | | | | ***Breakfast, Coffee and Check-in*** | 0:30 | 8:30 AM | 9:00 AM |
| | | Intro-2 | Vivek Bakshi | | EUV Litho | Welcome and Announcements | 0:10 | 9:00 AM | 9:10 AM |
| 1 | P1 | Keynote -1 | Allen | Gabor | IBM | Beyond High-NA EUV: A Dose-Window Framework for Stochastic Integrity at Future Nodes | 0:30 | 9:10 AM | 9:40 AM |
| 1 | P2 | Keynote -1 | Vineet | Vijayakrishnan Nair | Micron | Mask Wafer Co Optimization for High NA EUV Readiness in Advanced DRAM | 0:30 | 9:40 AM | 10:10 AM |
| | | | | | | **Break** | **0:20** | **10:10 AM** | **10:30 AM** |

| # | Paper # | Area | Presenter (First) | Presenter (Last) | Company | Title | Duration | Start | Finish |
|---|---|---|---|---|---|---|---|---|---|
| **Tuesday, June 9, 2026, Pauley Ballroom, UC Berkeley, CA** | | | | | | | | | |
| ***Session 2: Source - 1, Session Co-Chairs: TBA*** | | | | | | | | | |
| 2 | P76 | Source -1 | Oscar | Versolato | ARCNL | TBA | 0:15 | 10:30 AM | 10:45 AM |
| 2 | P74 | Source -1 | Hakaru | Mizoguchi | Kyushu university | EUV Exposure for Photo-Chemical Materials and LPP-EUV Source Research for Semiconductor Manufacturing II | 0:15 | 10:45 AM | 11:00 AM |
| 2 | P78 | Source -1 | Arun | Devaraj | PNNL | Accelerating Next-Generation EUV Lithography (ANGEL) through a Co-Design of Laser-Produced Plasma Sources and Multilayer Mirrors | 0:15 | 11:00 AM | 11:15 AM |
| 2 | P77 | Source -1 | Kentaro | Tomita | Hokkaido University | Control of the Ion Energy Distribution Function in Double-Pulse Laser-Produced EUV Plasmas | 0:15 | 11:15 AM | 11:30 AM |
| 2 | P75 | Source -1 | Tirtha | Joshi | UCSD | Scaling of EUV Conversion Efficiency with Material and Laser Intensity in High-Z Plasmas | 0:15 | 11:30 AM | 11:45 AM |
| 2 | P71 | Source -1 | Mats | Brinkman | ARCNL | Broadband EUV Imaging Spectrometry | 0:15 | 11:45 AM | 12:00 PM |
| 2 | P79 | Source -1 | Owen | Bardeen | UC San Diego | Pulse Conditioning and Material Comparisons for Optimized EUV and Beyond-EUV Emission from Laser-Produced Plasmas | 0:15 | 12:00 PM | 12:15 PM |
| | | | | | | **Lunch** | **1:00** | **12:15 PM** | **1:15 PM** |

| # | Paper # | Area | Presenter (First) | Presenter (Last) | Company | Title | Duration | Start | Finish |
|---|---|---|---|---|---|---|---|---|---|
| **Tuesday, June 9, 2026, Pauley Ballroom, UC Berkeley, CA** | | | | | | | | | |
| ***Session 3: Source - 2, Session Co-Chairs: TBA*** | | | | | | | | | |
| 3 | P72 | Source -2 | David | Reisman | Energetiq | EQS-10: A Next-Generation DPP EUV Light Source | 0:15 | 1:15 PM | 1:30 PM |
| 3 | P73 | Source -2 | Tomoyoshi | Toida | Gigaphoton | Development of Sn-LPP EUV Light Source for Actinic Mask Inspection | 0:15 | 1:30 PM | 1:45 PM |
| 3 | P80 | Source -2 | Hideyuki | Sera | Ushio | Comparative Collective Thomson Scattering Study of Single and Dual-Trigger LDP Tin Plasmas in an EUV Source | 0:15 | 1:45 PM | 2:00 PM |
| | | | | | | **Break** | **0:15** | **2:00 PM** | **2:15 PM** |

| # | Paper # | Area | Presenter (First) | Presenter (Last) | Company | Title | Duration | Start | Finish |
|---|---|---|---|---|---|---|---|---|---|
| **Tuesday, June 9, 2026, Pauley Ballroom, UC Berkeley, CA** | | | | | | | | | |
| ***Session 4: Resist and Patterning -1, Session Co-Chairs: TBA*** | | | | | | | | | |
| 4 | P47 | Resist and Patterning -1 | Anuja | De Silva | Lam | Dry Patterning Solutions Enabling High NA Lithography for Accelerated Feature Scaling | 0:15 | 2:15 PM | 2:30 PM |
| 4 | P53 | Resist and Patterning -1 | Stacey | Bent | Stanford | Molecular Layer Deposition of Metal Coordination Polymer Resists for EUV Lithography | 0:15 | 2:30 PM | 2:45 PM |
| 4 | P52 | Resist and Patterning -1 | Satinder | Sharma | SCEE/SCS | Iodine Functionalized Metal-Organic Cluster EUV Resists for High-Resolution Patterning with Fab-Compatible Processing | 0:15 | 2:45 PM | 3:00 PM |
| 4 | P51 | Resist and Patterning -1 | Iacopo | Mochi | PSI | Interference Lithography at EUV and Beyond at the XIL-II beamline | 0:15 | 3:00 PM | 3:15 PM |
| 4 | P50 | Resist and Patterning -1 | Ryan | Miyakawa | LBNL | Supporting Next-Gen EUVL: Hyper-NA and BEUV at CXRO | 0:15 | 3:15 PM | 3:30 PM |
| | | | | | | **Break** | **0:15** | **3:30 PM** | **3:45 PM** |

| # | Paper # | Area | Presenter (First) | Presenter (Last) | Company | Title | Duration | Start | Finish |
|---|---|---|---|---|---|---|---|---|---|
| **Tuesday, June 9, 2026, Pauley Ballroom, UC Berkeley, CA** | | | | | | | | | |
| ***Session 5: Supplier Showcase, Session Co-Chairs: TBA*** | | | | | | | | | |
| 5 | P95 | Supplier Showcase | Analía | Herrero | PTB | Soft X-rays for the Inspection of Complex Nanostructures and Thin-layers | 0:15 | 3:45 PM | 4:00 PM |
| 5 | P93 | Supplier Showcase | Jacqueline | van Veldhoven | TNO | EUV-Generated Plasma Characterization Using a Transparent RFEA | 0:15 | 4:00 PM | 4:15 PM |
| 5 | P94 | Supplier Showcase | Meng | Lee | Veeco | TBA | 0:15 | 4:15 PM | 4:30 PM |
| 5 | P92 | Supplier Showcase | Henry | Chou | Energetiq | TBA | 0:15 | 4:30 PM | 4:45 PM |
| 5 | P91 | Supplier Showcase | Matt | Hettermann | EUV Tech | Applications of EUV Metrology Tools | 0:15 | 4:45 PM | 5:00 PM |
| | | | | | | **Break** | **0:30** | **5:00 PM** | **5:30 PM** |

| # | Paper # | Area | Presenter (First) | Presenter (Last) | Company | Title | Duration | Start | Finish |
|---|---|---|---|---|---|---|---|---|---|
| **Tuesday, June 9, 2026, Pauley Ballroom, UC Berkeley, CA** | | | | | | | | | |
| ***Session 6: Poster Session, Session Chair: Vivek Bakshi (EUV Litho)*** | | | | | | | | | |
| | | | | | | **Poster Session and Reception** | 1:30 | 5:30 PM | 7:00 PM |
| 6 | P101 | Poster-Optics | Akira | Miyake | Toyama | The Development of EUV and Soft X-ray Optical Evaluation Systems in TOYAMA | | | |
| 6 | P102 | Poster-Resist and Patterning | Gahyun | Lee | Chonnam National University | T4(THP)4: Exploring Silicon-Based Inorganic Molecular Resists for Blue-X (6.7 nm) Lithography | | | |
| 6 | P103 | Poster-Resist and Patterning | Hayun | Kim | Chonnam National University | Dynamic Covalent Assembly(DCA)-Zinc Oxo Cluster Resists for EUV, Blue-X (6.7 nm) and Blue-X (3.1 nm) Lithography | | | |
| 6 | P104 | Poster-Resist and Patterning | Seungyong | Baek | Chonnam National University | Synthetic and Process Optimization of the Tin-Oxo Cluster CNU-TOC-01 toward Improved EUV Lithographic Performance | | | |
| 6 | P105 | Poster-Resist and Patterning | Hyun-Sung | Yoon | Chonnam National University | CASILON: A Core–Arm Siloxane Molecular Resist Candidate for Blue-X (6.7 nm) Lithography | | | |
| 6 | P106 | Poster-Resist and Patterning | Kenneth | Gonsalves | Indian Institute of Technology | Photoresists Beyond EUV: Revisiting X-ray Nanocomposite Resists - For Potential BEUVL | | | |
| 6 | P107 | Poster-Source | Wooram | Kim | Korea Research Institute of Standards and Science | Tabletop Extreme Ultraviolet (EUV) Testing Platform for Lithography Materials | | | |
| 6 | P108 | Poster-Source | Kyu Chang | Park | Kyung Hee University | Performance of EUV Light Source with Cold Field Emitters (CFEs) Beam Irradiation Technique | | | |

| # | Paper # | Area | Presenter (First) | Presenter (Last) | Company | Title | Duration | Start | Finish |
|---|---|---|---|---|---|---|---|---|---|
| 6 | P109 | Poster-Source | Matthew | Polek | PNNL | Dynamics of pre-pulsed laser-produced plasmas generated using mass limited Sn targets | | | |
| 6 | P110 | Poster-Source | Stanislav | Musikhin | PPPL | Multi-diagnostic experimental characterization of laser-produced tin plasmas | | | |
| 6 | P111 | Poster-Optics | Masatoshi | Hatayama | NTT | Development and Evaluation of Free-standing Mo/Si Multilayer Beam Splitters | | | |
| 6 | P112 | Poster - Metrology | TBA | | Inprentus | Maximize EUV and BEUV Instrument Performance with Custom Blazed, Variable-Line-Space Reflection Gratings on Flat or Curved Surfaces | | | |

| # | Paper # | Area | Presenter (First) | Presenter (Last) | Company | Title | Duration | Start | Finish |
|---|---|---|---|---|---|---|---|---|---|
| | | | | | | | | | |
| **Day 3: 2026 EUVL and Source Workshop** | | | | | | | | | |
| **8:30 AM - 4:30 PM, Wednesday, June 10, 2026, Pauley Ballroom, UC Berkeley, CA** | | | | | | | | | |
| ***Session 7: Keynote - 2, Session Chair: Ricardo Ruiz (LBNL)*** | | | | | | | | | |
| | | | | | | ***Breakfast, Coffee and Check-in*** | 0:30 | 8:30 AM | 9:00 AM |
| | | Intro-3 | Vivek Bakshi | | EUV Litho | Welcome and Announcements | 0:10 | 9:00 AM | 9:10 AM |
| 7 | P3 | Keynote -2 | Ronald | Goossens | ASML | The Amazing Longevity of Moore’s Law - 50 Years of Progress in Lithography | 0:30 | 9:10 AM | 9:40 AM |
| 7 | P4 | Keynote -2 | Laura | Waller | UC Berkeley /BETR Center | Computational Microscopy for EUV Lithography | 0:30 | 9:40 AM | 10:10 AM |
| | | | | | | **Break** | **0:20** | **10:10 AM** | **10:30 AM** |

| # | Paper # | Area | Presenter (First) | Presenter (Last) | Company | Title | Duration | Start | Finish |
|---|---|---|---|---|---|---|---|---|---|
| **Wednesday, June 10, 2026, Pauley Ballroom, UC Berkeley, CA** | | | | | | | | | |
| ***Session 8: Optics, Mask and Mask Metrology, Session Co-Chairs: TBA*** | | | | | | | | | |
| 8 | P26 | Optics, Mask and Mask Metrology | Sebastian | Brueck | Carl Zeiss | Advancements in ZEISS EUV Projection Optics: Enhancing Productivity and Enabling Shrink | 0:15 | 10:30 AM | 10:45 AM |
| 8 | P23 | Optics, Mask and Mask Metrology | Binyamin | Rubin | Veeco | In Situ Monitoring During Mo-Si Multilayer Deposition for EUV Mask Blanks : Concept and Simulation | 0:15 | 10:45 AM | 11:00 AM |
| 8 | P21 | Optics, Mask and Mask Metrology | Ayumi | Moriya | Hoya | Development of Capping Films Integrated with Mask Process for 1.X nm Node EUV Blanks | 0:15 | 11:00 AM | 11:15 AM |
| 8 | P24 | Optics, Mask and Mask Metrology | Stuart | Sherwin | EUV Tech | Harnessing the Power of Actinic Metrology for EUV Masks | 0:15 | 11:15 AM | 11:30 AM |
| 8 | P25 | Optics, Mask and Mask Metrology | Luke | Long | EUV Tech | TBA | 0:15 | 11:30 AM | 11:45 AM |
| 8 | P22 | Optics, Mask and Mask Metrology | Zachary | Levinson | Synopsys | Accurate Long Range Compact Modeling for Low-NA and High-NA EUV Mask Solutions | 0:15 | 11:45 AM | 12:00 PM |
| 8 | P27 | Optics, Mask and Mask Metrology | Dong Gun | Lee | E-Sol | Integrated Actinic EUV Tool for Mask Review, Reflectometry, High-speed CD, and Phase Measurement | 0:15 | 12:00 PM | 12:15 PM |
| | | | | | | **Lunch** | **1:00** | **12:15 PM** | **1:15 PM** |

| # | Paper # | Area | Presenter (First) | Presenter (Last) | Company | Title | Duration | Start | Finish |
|---|---|---|---|---|---|---|---|---|---|
| **Wednesday, June 10, 2026, Pauley Ballroom, UC Berkeley, CA** | | | | | | | | | |
| ***Session 9: Metrology, Session Co-Chairs: TBA*** | | | | | | | | | |
| 9 | P34 | Metrology | Ahmed | Diallo | PPPL | SparkLight: A New Platform for Laser-Produced Plasma Research in Support of Next-Generation EUV Lithography | 0:15 | 1:15 PM | 1:30 PM |
| 9 | P31 | Metrology | Stephanie | Moffitt | NIST | New Developments at the Synchrotron Ultraviolet Radiation Facility (SURF III) | 0:15 | 1:30 PM | 1:45 PM |
| 9 | P32 | Metrology | Brian | Simonds | NIST | Progress on the NIST Deployable Absolute EUV Radiometer | 0:15 | 1:45 PM | 2:00 PM |
| 9 | P33 | Metrology | Jiho | Kim | Pohang/POSTECH | Actinic EUV/Blue-X Characterization for Advanced Materials and Lithography Applications | 0:15 | 2:00 PM | 2:15 PM |
| | | | | | | **Break** | **0:15** | **2:15 PM** | **2:30 PM** |

| # | Paper # | Area | Presenter (First) | Presenter (Last) | Company | Title | Duration | Start | Finish |
|---|---|---|---|---|---|---|---|---|---|
| **Wednesday, June 10, 2026, Pauley Ballroom, UC Berkeley, CA** | | | | | | | | | |
| ***Session 10: Sources Modeling, Session Co-Chairs: TBA*** | | | | | | | | | |
| 10 | P85 | Source - Modeling | Igor | Golovkin | Prism Computations | Atomic Data and Collisional-Radiative Atomic Kinetics Simulations for EUV/x-ray Sources | 0:15 | 2:30 PM | 2:45 PM |
| 10 | P81 | Source - Modeling | John | Sheil | ARCNL | TBA | 0:15 | 2:45 PM | 3:00 PM |
| 10 | P82 | Source - Modeling | James | Colgan | LANL | Effective Temperature Approximations for Use in Modeling Non-LTE Tin Plasmas | 0:15 | 3:00 PM | 3:15 PM |
| 10 | P83 | Source - Modeling | Mark | Sherlock | LLNL | Quantum Effects in the Absorption of Laser Light by EUV-Source Relevant Plasmas | 0:15 | 3:00 PM | 3:15 PM |
| 10 | P84 | Source - Modeling | Kirill | Lezhnin | PPPL | Simulating Fast Ion Debris for Next-Generation Light Sources for Nanolithography | 0:15 | 3:15 PM | 3:30 PM |
| 10 | P86 | Source - Modeling | Akira | Sasaki | QST | Investigation of Atomic Processes and Radiative Transfer in Tin Plasmas for Updating the Opacity Table | 0:15 | 3:15 PM | 3:30 PM |
| 10 | P87 | Source - Modeling | Nozomi | Tanaka | University of Osaka | Optimization of EUV Output by Experimentally Validated Radiation-Hydrodynamic Simulations Across a Broad Laser Parameter Space | 0:15 | 3:30 PM | 3:45 PM |
| | | | | | | **Break** | **0:45** | **3:45 PM** | **4:30 PM** |
| | | | | | | **UC Berkeley Campus Walking Tour** | **1:00** | **4:30 PM** | **5:30 PM** |

| # | Paper # | Area | Presenter (First) | Presenter (Last) | Company | Title | Duration | Start | Finish |
|---|---|---|---|---|---|---|---|---|---|
| | | | | | | | | | |

# Day 4: 2026 EUVL and Source Workshop

## 9:30 AM - 4:30 PM, Thursday, June 11, 2026, Pauley Ballroom, UC Berkeley, CA

| # | Paper # | Area | Presenter (First) | Presenter (Last) | Company | Title | Duration | Start | Finish |
|---|---|---|---|---|---|---|---|---|---|
| | | | | | | ***Session 11: Lasers, Session Chair: TBA*** | | | |
| | | | | | | ***Breakfast, Coffee and Check-in*** | 0:30 | 9:30 AM | 10:00 AM |
| | | Intro-4 | Vivek Bakshi | | EUV Litho | Welcome and Announcements | 0:05 | 10:00 AM | 10:05 AM |
| 11 | P14 | Lasers | Jens | Brunne | Trumpf | Scaling Efficiency and Power in $CO_2$ Drive Lasers for EUV | 0:15 | 10:05 AM | 10:20 AM |
| 11 | P16 | Lasers | Emily | Sistrunk Link | LLNL | High Energy Solid-State λ ≈ 2 µm Laser Drivers for Efficient EUV and Plasma Sources | 0:15 | 10:20 AM | 10:35 AM |
| 11 | P11 | Lasers | Tobias | Heuermann | AFS | 2µm Fiber Lasers as Efficient Next Generation EUV Drive Lasers | 0:15 | 10:35 AM | 10:50 AM |
| 11 | P15 | Lasers | Joachim | Gräfe | Trumpf | A Scalable 2 µm Laser Platform for Next Generation EUV Light Sources | 0:15 | 10:50 AM | 11:05 AM |
| 11 | P13 | Lasers | Ryo | Yasuhara | National Institute for Fusion | Development of a High-Power 3–4 µm Mid-Infrared Laser for High-Efficiency EUV Light Sources | 0:15 | 11:05 AM | 11:20 AM |
| 11 | P12 | Lasers | Robert | Klas | Fraunhofer IOF | Power Scalable Highly Efficient High Harmonic Generation at 13.5 nm Using a Visible-Driving Laser | 0:15 | 11:20 AM | 11:35 AM |
| | | | | | | **Break** | **0:15** | **10:35 AM** | **10:50 AM** |

| # | Paper # | Area | Presenter (First) | Presenter (Last) | Company | Title | Duration | Start | Finish |
|---|---|---|---|---|---|---|---|---|---|
| **Thursday, June 11, 2026, Pauley Ballroom, UC Berkeley** | | | | | | | | | |
| ***Session 12: Laser Wakefield Accelerator (LWFA), Session Co-Chairs: TBA*** | | | | | | | | | |
| 12 | P17 | Laser Wakefield Accelerator | Finn | Kohrell | LBNL | Compact Free-Electron Lasing at BELLA Center's Laser-Plasma Accelerator | 0:15 | 10:50 AM | 11:05 AM |
| 12 | P18 | Laser Wakefield Accelerator | Manuel | Kirchen | Deutsches Elektronen-Synchrotron | Laser–Plasma Accelerators and Their Potential to Drive EUV Light Sources | 0:15 | 11:05 AM | 11:20 AM |
| 12 | P19 | Laser Wakefield Accelerator | Stephen | Milton | TAU Systems | TAU Systems Inc.: Bringing Laser-Powered Accelerator Systems to the Commercial Market | 0:15 | 11:20 AM | 11:35 AM |
| 12 | P20 | Laser Wakefield Accelerator | | | TBA | TBA | 0:15 | 11:35 AM | 11:50 AM |
| | | | | | | **Lunch** | **1:10** | **11:50 AM** | **1:00 PM** |

| # | Paper # | Area | Presenter (First) | Presenter (Last) | Company | Title | Duration | Start | Finish |
|---|---|---|---|---|---|---|---|---|---|
| **Thursday, June 11, 2026, Pauley Ballroom, UC Berkeley** | | | | | | | | | |
| ***Session 13: Resist and Patterning 2, Session Co-chairs: TBA*** | | | | | | | | | |
| 13 | P55 | Resist and Patterning -2 | Takahiro | Kozawa | University of Osaka | Development of Resist Materials under JST K Program | 0:15 | 1:00 PM | 1:15 PM |
| 13 | P42 | Resist and Patterning -2 | Chang-Yong | Nam | Brookhaven National Lab | EUV Research Activities and Infrastructure Development at BNL (Invited) | 0:15 | 1:15 PM | 1:30 PM |
| 13 | P48 | Resist and Patterning -2 | Ricardo | Ruiz | LBNL | Navigating Chemical Stochasticity in EUV Lithography: CHiPPS Materials Platforms and Metrology | 0:15 | 1:30 PM | 1:45 PM |
| | | | | | | **Break** | **0:15** | **1:45 PM** | **2:00 PM** |

| # | Paper # | Area | Presenter (First) | Presenter (Last) | Company | Title | Duration | Start | Finish |
|---|---|---|---|---|---|---|---|---|---|
| **Thursday, June 11, 2026, Pauley Ballroom, UC Berkeley** | | | | | | | | | |
| ***Session 14: Resist and Patterning -3 , Session Co-chairs: TBA*** | | | | | | | | | |
| 14 | P46 | Resist and Patterning -3 | Michael | Tsapatsis | John Hopkins University | Amorphous Zeolitic Imidazolate Frameworks (aZIF) as Resists for EUV and BEUV Lithography | 0:15 | 2:00 PM | 2:15 PM |
| 14 | P54 | Resist and Patterning -3 | Congque | Dinh | TEL | Holistic Integration of Novel Patterning Technologies for High-NA EUV Lithography | 0:15 | 2:15 PM | 2:30 PM |
| 14 | P49 | Resist and Patterning -3 | Samuel | Blau | LBNL | Discovering EUV Photoresist Chemistry through Automated Reaction Network Construction and Spatiotemporal Kinetic Simulation | 0:15 | 2:30 PM | 2:45 PM |
| 14 | P56 | Resist and Patterning -3 | Kyunghyeon | Lee | University of Chicago | Design of block copolymers for directed self-assembly to mitigate stochastic challenges in EUV lithography | 0:15 | 2:45 PM | 3:00 PM |
| 14 | P45 | Resist and Patterning -3 | Jiwon | Kim | Hanyang Univ/CH3IPS | Defect-Free EUV Patterning of Metal Oxide Resists using Cl2/Ar LET Plasma Dry Development for High-Fidelity Etch Transfer | 0:15 | 3:00 PM | 3:15 PM |
| 14 | P57 | Resist and Patterning -3 | Jiyoung | Kim | UT Dallas | Dry Developing Process of Molecular-Atomic-Layer-Deposited Hybrid Dry Photoresist for EUV Lithography | 0:15 | 3:15 PM | 3:30 PM |
| 14 | P41 | Resist and Patterning -3 | Nikhil | Tiwale | BNL | Positive-Tone Hybrid EUV Resists Synthesized by Vapor Phase Infiltration | 0:15 | 3:30 PM | 3:45 PM |
| | | | | | | **Announcements** | **0:15** | **3:45 PM** | **4:00 PM** |
| | | | | | | **Break** | **0:30** | **4:00 PM** | **4:30 PM** |
| | | | | | | **Buses Depart for Dinner Cruise** | | **4:30 PM** | |
| | | | | | | **Workshop Dinner Cruise** | **3:30** | **5:30 PM** | **9:00 PM** |
| **Workshop Adjourned** | | | | | | | | | |